REMARKS

In view of the above amendments and the following remarks, reconsideration of the rejections contained in the Office Action of September 21, 2007 is respectfully requested.

By this Amendment, claim 1 has been amended and new claim 12 has been added. Thus, claims 1-12 are currently pending in the application. No new matter has been added by these amendments.

On page 2 of the Office Action, the Examiner rejected claims 1-11 under 35 U.S.C. § 102(b) as being anticipated by Fujitani et al. (JP 2003-054991). For the reasons discussed below, it is respectfully submitted that the amended claims are clearly patentable over the prior art of record.

Amended independent claim 1 recites a plasma display panel comprising a front panel including a display electrode, a dielectric layer and a protective layer sequentially formed on a first glass substrate. The plasma display panel of claim 1 also comprises a back panel including an address electrode, a base dielectric layer, a barrier rib and a phosphor layer sequentially formed on a second glass substrate. Claim 1 also recites that the front panel and the back panel are disposed so as to oppose each other and are sealed at peripheries of the front panel and the back panel with a sealing member so as to define an inner space between the front panel and the back panel. Claim 1 further recites that a catalyst for reacting with a hydrocarbon is provided so as to be exposed to the inner space.

Fujitani discloses a plasma display panel (PDP) which, as shown in Fig. 1, includes a front panel 101 and a back panel 111. The front panel 101 includes a dielectric layer 104, and a protective layer 105 covering the dielectric layer 104.

However, Fujitani does not disclose that the front panel and the back panel are disposed so as to oppose each other and are sealed at peripheries of the front panel and the back panel with a sealing member so as to define an inner space between the front panel and the back panel, and that a catalyst is provided so as to be exposed to the inner space, as required by amended independent claim 1. Rather, Fujitani discloses that the dielectric layer 104 is made from a dielectric layer precursor 104a, which as shown in Fig. 4 includes glass powder 1040, a

dispersant 1041 and a decomposition accelerating material 1042. As explained in paragraph [0012], Fujitani discloses that due to the decomposition accelerating material, organic material (such as resin in the dispersant) is decomposed quickly such that when the glass powder is melted to form the dielectric layer 104, gas generated from the decomposition of the organic material will not become trapped in the resulting dielectric layer 104.

However, in the PDP as seen in Fig. 1, the dielectric layer 104 is covered by the protective layer 105. In other words, the dielectric layer 104 is not exposed to the inner space between the front and back panels, and therefore any catalyst contained in the dielectric layer 104 is also not exposed to the inner space, as required by independent claim 1.

In this regard, it is noted that on page 4 of the Office Action, the Examiner asserts that the protective layer 105 is not present during the decomposition of the dielectric precursor when the catalyst is utilized, as shown in Figs. 2(c)-(e) of Fujitani. Therefore, the Examiner concludes that Fujitani discloses a catalyst to be exposed to the inner space because the catalyst is utilized prior to the formation of the protective layer 105.

As indicated above, it is noted that the plasma display panel of amended independent claim 1 includes a front panel having a protective layer, and that the front panel and the back panel are disposed so as to oppose each other and are sealed at peripheries of the front panel and the back panel with a sealing member so as to define an inner space between the front panel and the back panel. Fujitani, however, discloses that the catalyst is utilized during the formation of the dielectric layer (i.e., prior to the front and back panels being sealed together). Therefore, Fujitani does not disclose a catalyst to be exposed to an inner space defined between a front panel and a back panel disposed so as to oppose each other and sealed at peripheries of the front panel and the back panel with a sealing member, because Fujitani only discloses a catalyst being exposed to a space while forming the dielectric layer on a front panel which is not yet sealed with a back panel by a sealing member.

Further, Fujitani does not disclose a catalyst to be exposed to an inner space defined between a back panel and a front panel which includes a protective layer, as required by amended independent claim 1. Rather, as indicated above, Fujitani discloses that the catalyst is utilized prior to the formation of the protective layer, and therefore does not disclose a catalyst to be

exposed to an inner space defined between a back panel and <u>a front panel which includes a</u> protective layer.

Therefore, it is respectfully submitted that independent claim 1, as well as claims 2-12 which depend therefrom, are clearly allowable over the prior art of record.

In addition, the Examiner's attention is directed to the dependent claims which further define the present invention over the prior art. For example, dependent claim 12 recites that the inner space is defined between the protective layer of the front panel and the phosphor layer, barrier rib and base dielectric layer of the back panel. As stated above, Fujitani discloses that the catalyst is utilized during the formation of the dielectric layer (*i.e.*, prior to the front and back panels being sealed together) and prior to the formation of the protective layer. Therefore, Fujitani does not disclose a catalyst to be exposed to an inner space defined between the protective layer of the front panel and the phosphor layer, barrier rib and base dielectric layer of the back panel, as required by dependent claim 12.

In view of the foregoing amendments and remarks, it is respectfully submitted that the present application is clearly in condition for allowance. An early notice to that effect is respectfully solicited.

If, after reviewing this Amendment, the Examiner feels there are any issues remaining which must be resolved before the application can be passed to issue, the Examiner is respectfully requested to contact the undersigned by telephone in order to resolve such issues.

Respectfully submitted,

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